

Form PTO-1449 (MODIFIED)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 032026:0777		SERIAL NO. 10/ 800,923	
INFORMATION DISCLOSURE CITATION Submitted: March 15, 2004 <i>(Use several sheets if necessary)</i>				APPLICANT Paul F. Nealey, et al.			
				FILING DATE		GROUP ART UNIT 1756	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
FOREIGN PATENT DOCUMENTS							
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION YES NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
PD		T.A. Savas, et al., "Achromatic Interferometric Lithography for 100-nm-Period Gratings and Grids," J. Vac. Sci. Technol. B, Vol. 13, No. 6, Nov./Dec., 1995, pp. 2732-2735.					
PD		T.A. Savas, et al., "Large-Area Achromatic Interferometric Lithography for 100 nm Period Gratings and Grids," J. Vac. Sci. Technol. B, Vol. 14, No. 6, Nov./Dec., 1996, pp. 4167-4170.					
PD		P. Mansky, et al., "Ordered Diblock Copolymer Films on Random Copolymer Brushes," Macromolecules, Vol. 30, 1997, pp. 6810-6813.					
PD		Xiaolan Chen, et al., "Interferometric Lithography of Sub-Micrometer Sparse Hole Arrays for Field-Emission Display Applications," J. Vac. Sci. Technol. B, Vol. 14, No. 5, Sep./Oct., 1996, pp. 3339-3349.					
PD		Miri Park, et al., "Block Copolymer Lithography: Periodic Arrays of ~1011 Holes in 1 Square Centimeter," Science, Vol. 276, No. 5317, 30 May 1997, pp. 1401-1404.					
EXAMINER <i>Stephen Charles Davis</i>				DATE CONSIDERED 09/23/04			
* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.							

Form PTO-1449 (MODIFIED)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 032026-0777	SERIAL NO. 10/800923
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
P/D		Hideaki Yokoyama, et al., "Structure and Diffusion of Asymmetric Diblock Copolymers in Thin Films: A Dynamic Secondary Ion Mass Spectrometry Study," <i>Macromolecules</i> , Vol. 31, 1998, published on web 11/20/98, pp. 8826-8830.	
P/D		Wieland Schöllkopf, et al., "A Cluster Size Nanofilter with Variable Openings Between 2 and 50 nm," <i>J. of Chemical Physics</i> , Vol. 109, No. 21, 1 December 1998, pp. 9252-9257.	
P/D		J.A. Hoffnagle, et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography," <i>J. Vac. Sci. Technol. B</i> , Vol. 17, No. 6, Nov./Dec., 1999, pp. 3306-3309.	
P/D		Christopher Harrison, et al., "Reducing Substrate Pinning of Block Copolymer Microdomains with a Buffer Layer of Polymer Brushes," <i>Micromolecules</i> , Vol. 33, 2000, published on web 12/28/99, pp. 857-865.	
P/D		Rob G.H. Lammertink, et al., "Nanostructured Thin Films of Organic-Organometallic Block Copolymers: One-Step Lithography with Poly(ferrocenylsilanes) by Reactive Ion Etching," <i>Advanced Materials</i> , Vol. 12, No. 2, 2000, pp. 98-102.	
P/D		Thomas Thurn-Albrecht, et al., "Nanoscale Templates from Oriented Block Copolymer Films," <i>Advanced Materials</i> , Vol. 12, No. 11, 2000, pp. 787-791.	
P/D		Augustine Urbas, et al., "Tunable Block Copolymer/Homopolymer Photonic Crystals," <i>Advanced Materials</i> , Vol. 12, No. 11, pp. 812-814.	
P/D		Didier Benoit, et al., "One-Step Formation of Functionalized Block Copolymers," <i>Macromolecules</i> , Vol. 33, 2000, published on web 2/12/00, pp. 1505-1507.	
P/D		Richard D. Peters, et al., "Using Self-Assembled Monolayers Exposed to X-Rays to Control the Wetting Behavior of Thin Films of Diblock Copolymers," <i>Langmuir</i> , Vol. 16, 2000, published on web 4/7/00, pp. 4625-4631.	
P/D		V.Y. Banine, et al., "Comparison of Extreme Ultraviolet Sources for Lithography Applications," <i>Micron</i> , Vol. 31, 2000, pp. 681-684.	
P/D		Qiang Wang, et al., "Symmetric Diblock Copolymer Thin Films Confined Between Homogeneous and Patterned Surfaces: Simulations and Theory," <i>J. of Chemical Physics</i> , Vol. 112, No. 22, 8 June 2000, pp. 9996-10010.	

Form PTO-1449 (MODIFIED)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 032026-0601	SERIAL NO. 10/800,923
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)					
PD		Jakob Heier, et al., "Kinetics of Individual Block Copolymer Island Formation and Disappearance Near an Absorbing Boundary," <i>Macromolecules</i> , Vol. 33, 2000, published on web 7/12/00, pp. 6060-6067.			
PD		Yachin Cohen, et al., "Deformation of Oriented Lamellar Block Copolymer Films," <i>Macromolecules</i> , Vol. 33, 2000, published on web 8/5/00, pp. 6502-6516.			
PD		M. Switkes, et al., "Patterning of Sub-50 nm Dense Features with Space-Invariant 157 nm Interference Lithography," <i>Applied Physics Letters</i> , Vol. 77, No. 20, 13 November 2000, pp. 3149-3151.			
PD		Tae K. Kim, et al., "Chemical Modification of Self-Assembled Monolayers by Exposure to Soft X-Rays in Air," <i>J. Phys. Chem. B</i> , Vol. 104, 2000, published on web, 7/18/00, pp. 7403-7410.			
PD		Richard D. Peters, et al., "Combining Advanced Lithographic Techniques and Self-Assembly of Thin Films of Diblock Copolymers to Produce Templates for Nanofabrication," <i>J. Vac. Sci. Technol. B</i> , Vol. 18, No. 6, Nov./Dec., 2000, pp. 1-5.			
PD		T. Thum-Albrecht, et al., "Ultrahigh-Density Nanowire Arrays Grown in Self-Assembled Diblock Copolymer Templates," <i>Science</i> , Vol. 290, No. 5499, 15 December 2000, pp. 2126-2129.			
PD		Xiao M. Yang, et al., "Guided Self-Assembly of Symmetric Diblock Copolymer Films on Chemically Nanopatterned Substrates," <i>Macromolecules</i> , Vol. 33, 2000, published on web 12/26/00, pp. 9575-9582.			
PD		Alexander C. Edrington, et al., "Polymer-Based Photonic Crystals," <i>Advanced Materials</i> , Vol. 13, No. 6, March 16, 2001, pp. 421-425.			
PD		C.T. Black, et al., "Integration of Self-Assembled Diblock Copolymers for Semiconductor Capacitor Fabrication," <i>Applied Physics Letters</i> , Vol. 79, No. 3, 16 July 2001, pp. 409-411.			
PD		A. Yen, et al., "Achromatic Holographic Configuration for 100-nm-Period Lithography," <i>Applied Optics</i> , Vol. 31, No. 22, August 1, 1992, pp. 4540-4545.			
PD		H.H. Solak, et al., "Exposure of 38 nm Period Gratings Patterns with Extreme Ultraviolet Interferometric Lithography," <i>Applies Physics Letters</i> , Vol. 75, 1999, pp. 2328-2330.			

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MD		Yang, X. M. et al., "Patterning of self-assembled monolayers with lateral dimensions of 0.15 μm using advanced lithography," <i>J. Vac. Sci. Technol. B</i> , 17(6), Nov/Dec 1999, pp. 3203-3207; published by American Vacuum Society.					
MD		Peters, R. D. et al., "Combining advanced lithographic techniques and self-assembly of thin films of diblock copolymers to produce templates for nanofabrication," <i>J. Vac. Sci. Technol. B</i> , 18(6), Nov/Dec 2000, pp. 3530-3534; published by American Vacuum Society.					
MD		Yang, X. M. et al., "Proximity X-ray Lithography Using Self-Assembled Alkylsiloxane Films: Resolution and Pattern Transfer," <i>Langmuir</i> , 2001, 17, pp. 228-233; published by American Chemical Society.					
MD		Wang, Q. et al., "Monte Carlo simulations of diblock copolymer thin films confined between two homogeneous surfaces," <i>Journal of Chemical Physics</i> , 112(1), 1 January 2000; published by American Institute of Physics.					
MD		Wang, Q. et al., "Monte Carlo Simulations of Diblock Copolymer Thin Films Confined between Chemically Heterogeneous Hard Surfaces," <i>Macromolecules</i> , 2000, 33, pp. 4512-4525; published by American Chemical Society.					
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MD		Nath, S. K. et al., "Density functional theory of molecular structure for thin diblock copolymer films on chemically heterogeneous surfaces," <i>Journal of Chemical Physics</i> , 110(15), 15 April 1999; published by American Institute of Physics.					
MD		Solak, H. H. et al., "EUV Interferometric Lithography for Resist Characterization," SPIE, Vol. 3676, Santa Clara, California, March 1999.					